

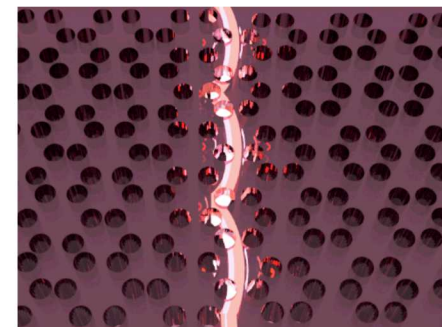
Optical Frequency Topological Photonic Structures

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Sandia National Laboratories, Albuquerque, NM

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and Stavroula Foteinopoulou (Univ. of NM)**

**Aug 11-15, 2019 ,SPIE Optics and Photonics
San Diego, CA, USA**



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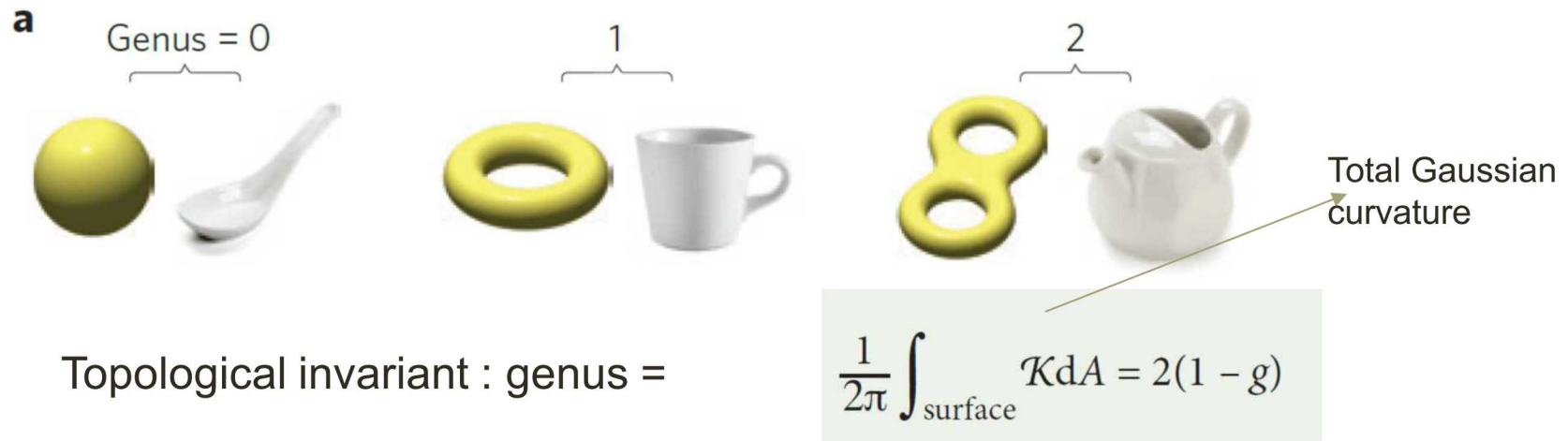


Outline

- Brief Introduction
- Pseudo spin based all dielectric topological structure
- Silicon-on-insulator (SOI) implementation
- III-nitride
- Summary

Topological Protection

Topological Protection: Approaches that exploit topological properties of the phase space of a system can offer stability and robustness to the system of interest from external disturbances such as scattering, decoherence etc.



- Need to create a topological transition to affect the system.

➤ Non-trivial topological system can provide new ways of control in electronics and **photonics**. (Eg. Loss-less unidirectional, scatter-free transport)

L. Lu, J. D. Joannopoulos, and M. Soljacic, "Topological photonics," Nat Photon **8**, 821-829 (2014).

Topological Photonics Research Activities

PHYSICAL REVIEW A 78, 033834 (2008)

Analog of quantum-Hall-effect edge states in photonic crystals

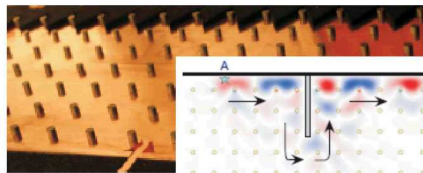
S. Raghu*

Department of Physics, Stanford University, Stanford, California 94305-4045, USA

F. D. M. Haldane

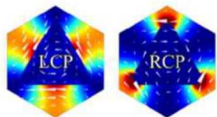
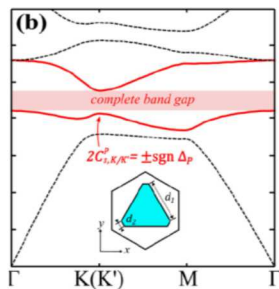
Department of Physics, Princeton University, Princeton, New Jersey 08544-0708, USA

One-way transport at microwave frequency



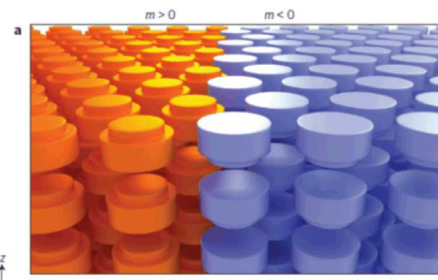
Z. Wang, Y. Chong, et.al. ,
Nature **461**, 772 (2009).

Valley hall PTI



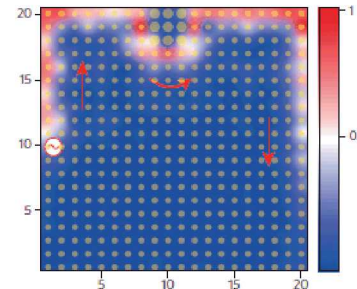
M. Tzuhuan and S. Gennady,
NJP.**18** (2), 025012 (2016).

3D All dielectric PTI



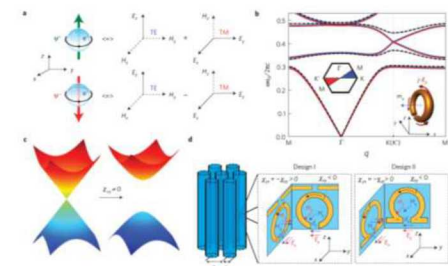
A. Slobozhanyuk, et.al. , Nat
Photon **11** (2), 130-136 (2017).

One-way edge transport



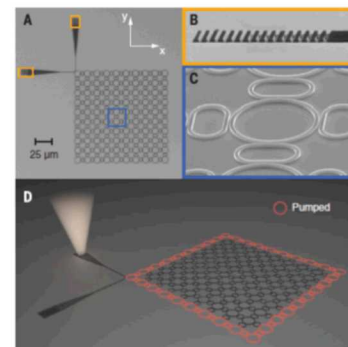
K.Fang, Z. Yu , S.H.Fan ,
Nat. Phot. **6** , (2012)

Metamaterial PTI



A. B. Khanikaev et.al. Nat
Mater **12** (3), 233-239 (2013).

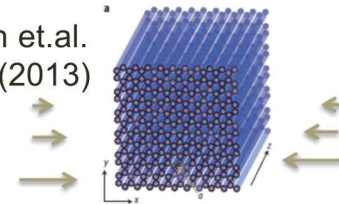
PTI lasing



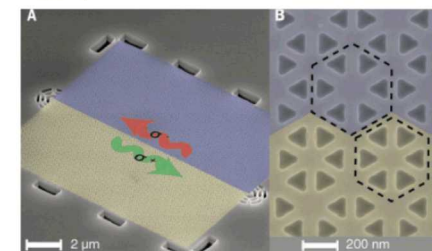
Bandres, M. A. et al. Science
359, eaar1231 (2018).

Strain induced pseud mag. field in optical fiber arrays

M.Rechtsman et.al.
Nat. Phot. **7** (2013)



Topological edge states in III-V



Barik, S. et al.. Science
359, 666 (2018).

Topological Photonics Spin Hall in Dielectric PC

PRL 114, 223901 (2015)

PHYSICAL REVIEW LETTERS

week ending
5 JUNE 2015

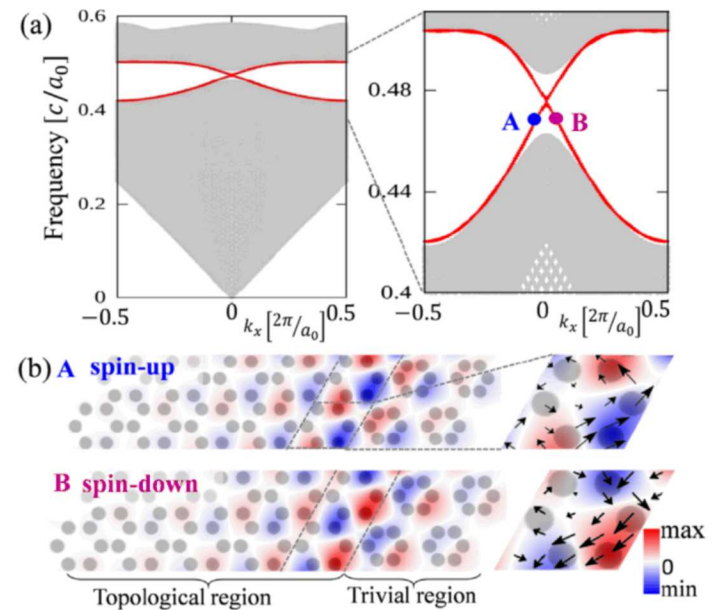
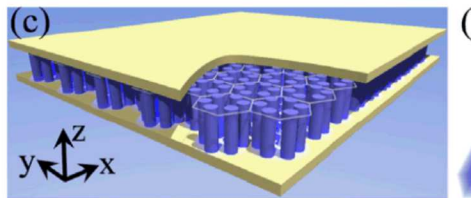
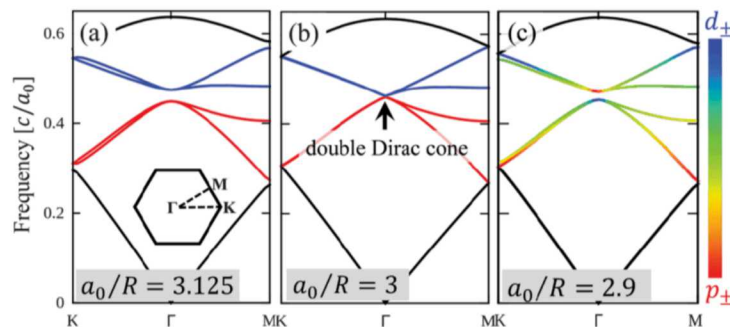
Scheme for Achieving a Topological Photonic Crystal by Using Dielectric Material

Long-Hua Wu and Xiao Hu*

*International Center for Materials Nanoarchitectonics (WPI-MANA), National Institute for Materials Science,
Tsukuba 305-0044, Japan*

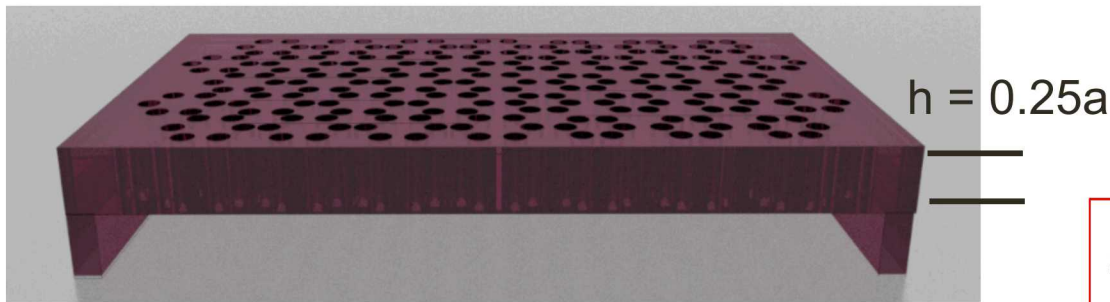
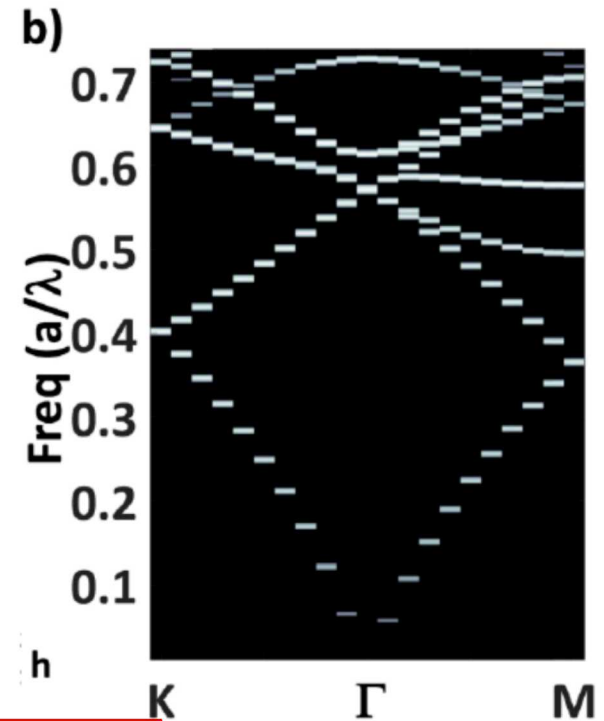
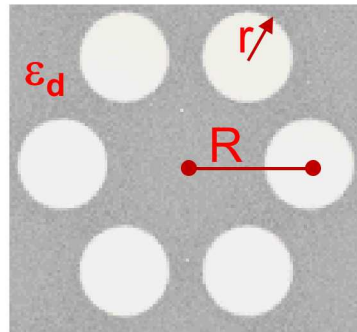
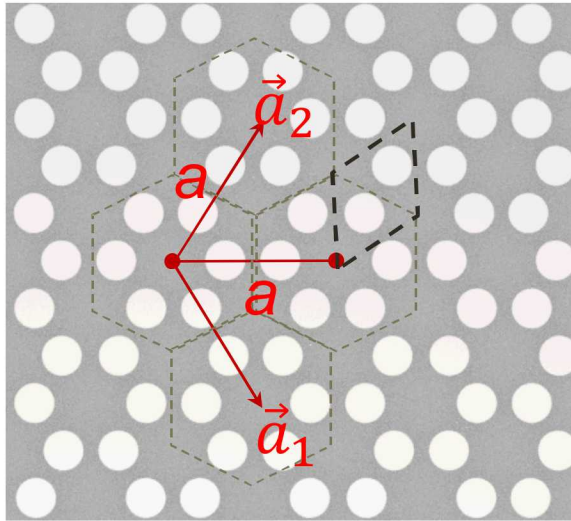
Graduate School of Pure and Applied Sciences, University of Tsukuba, Tsukuba 305-8571, Japan

(Received 10 February 2015; published 3 June 2015)



Modified honeycomb lattice of hexagonal cylindrical dielectric rods

Thin-slab Photonic Crystal Design

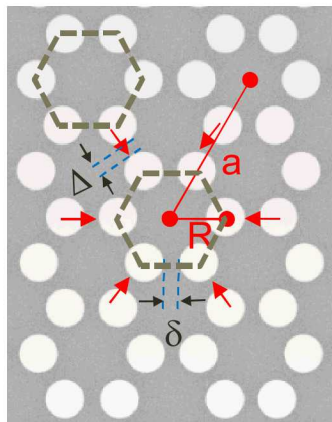


$$\begin{aligned} a/R &= 3.0 \\ r &= 0.13a \end{aligned}$$

Calculated with FDTD (Lumerical ®)

Circular Hole Array Honeycomb Lattice Photonic Crystal

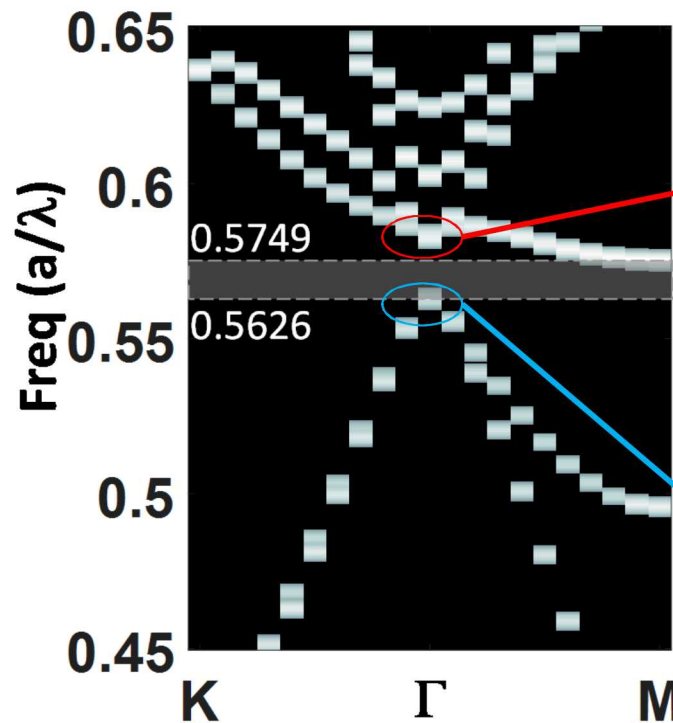
Compressed lattice $a/R = 3.1$



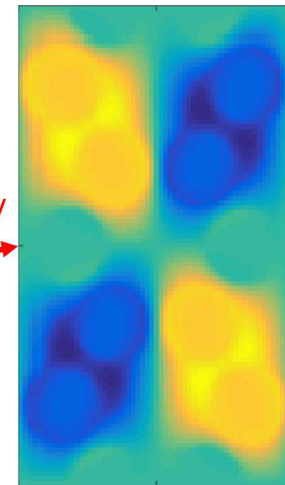
$$\Delta = a - 2(R + r)$$

$$\delta = R - 2r$$

Topologically Trivial PC



d_{xy}

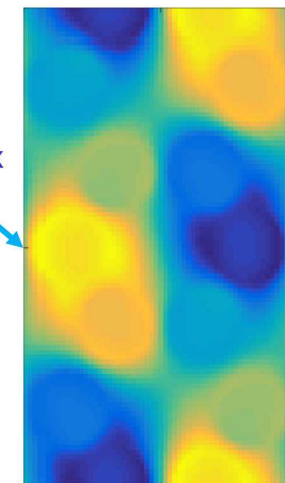


Re(Hz)

Max

Min

p_x

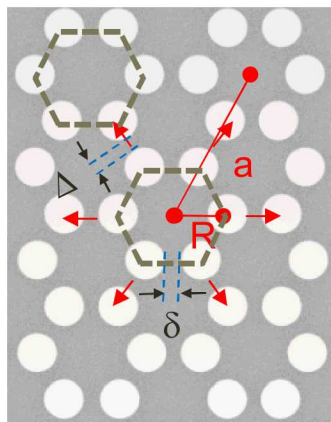


Max

Min

Circular Hole Array Honeycomb Lattice Photonic Crystal

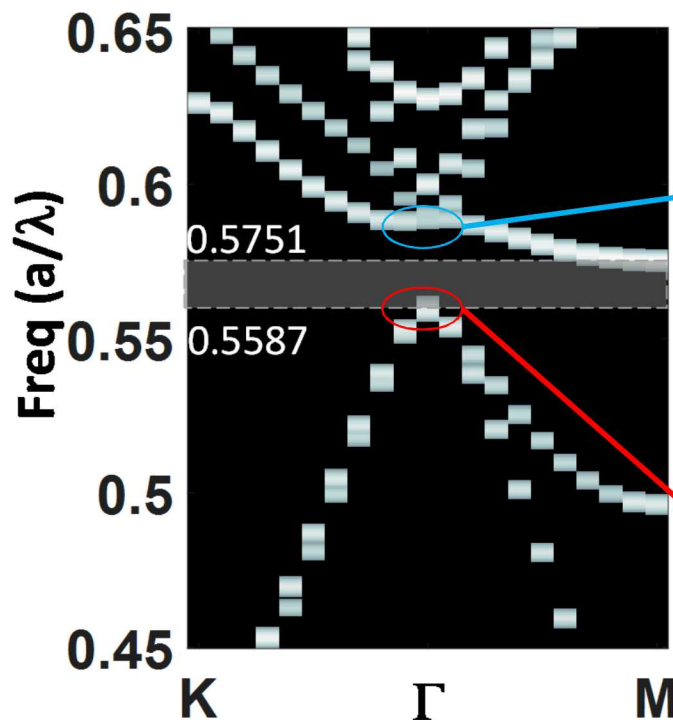
Expanded lattice $a/R = 2.9$



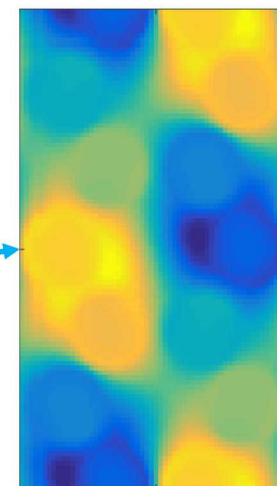
$$\Delta = a - 2(R + r)$$

$$\delta = R - 2r$$

Topologically Non-trivial PC



p_x

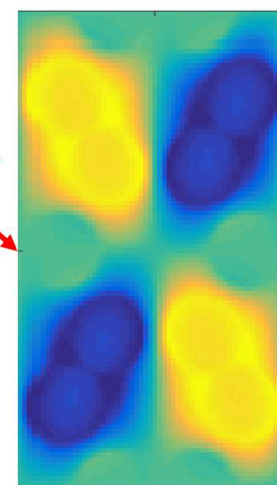


Re(Hz)

Max

Min

d_{xy}



Max

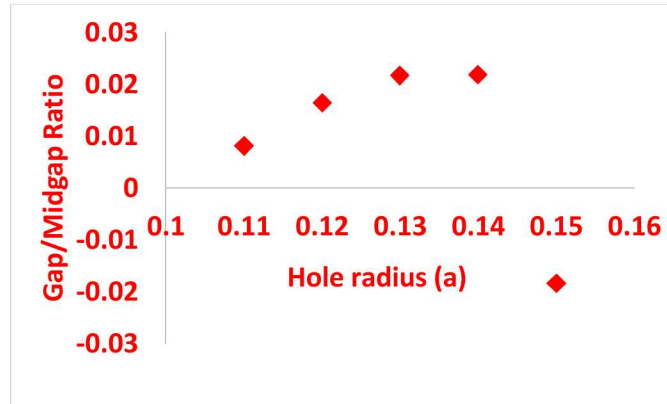
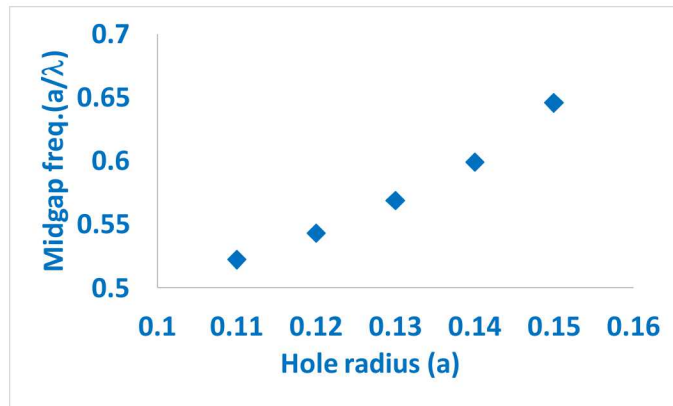
Min

Circular Hole Array Honeycomb Lattice Photonic Crystal

Hole radius 'r' dependence

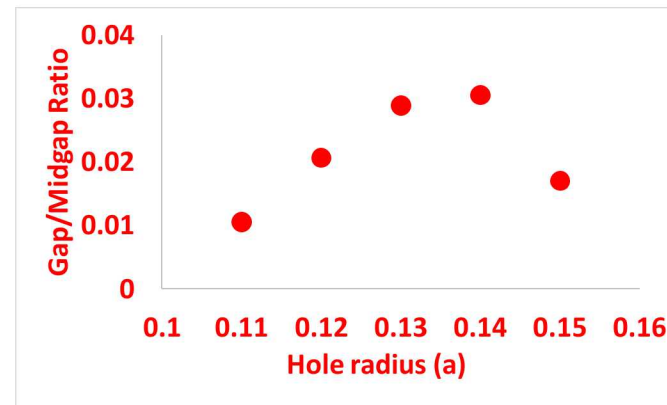
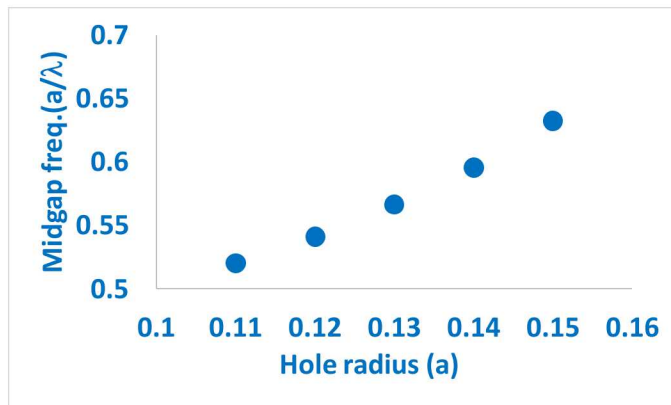
Compressed $a/R = 3.1$

Membrane thickness
'h' = $0.25a$



At $\lambda \sim 1500\text{nm}$
 $\Delta\lambda \sim 30\text{nm}$

Expanded $a/R = 2.9$

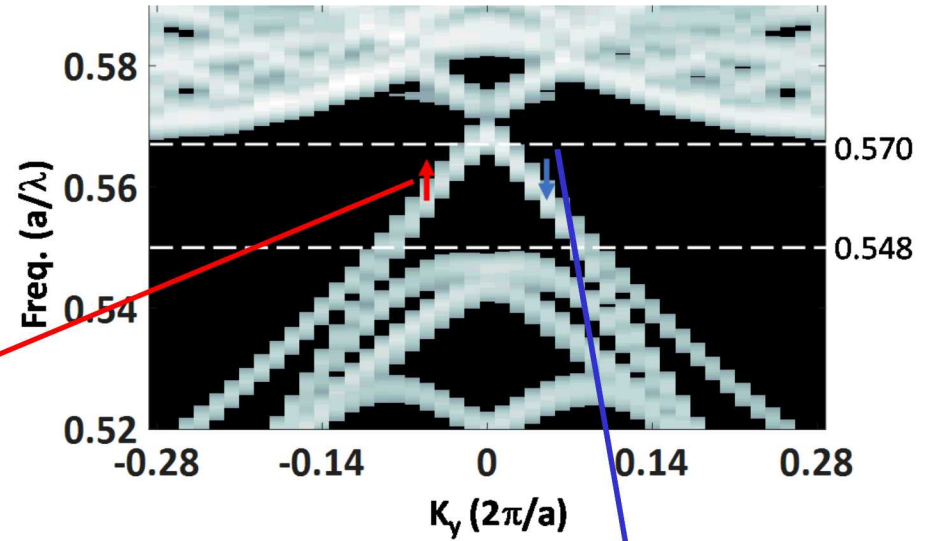
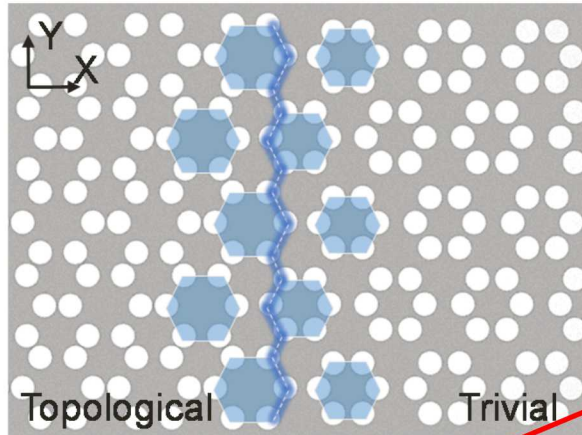


At $\lambda \sim 1500\text{nm}$
 $\Delta\lambda \sim 45\text{nm}$

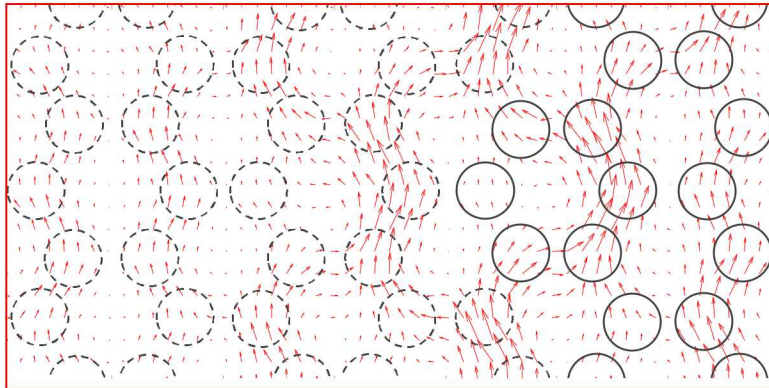
Reasonable operational bandwidth possible at the telecom frequencies

Unidirectional Edge State Propagation

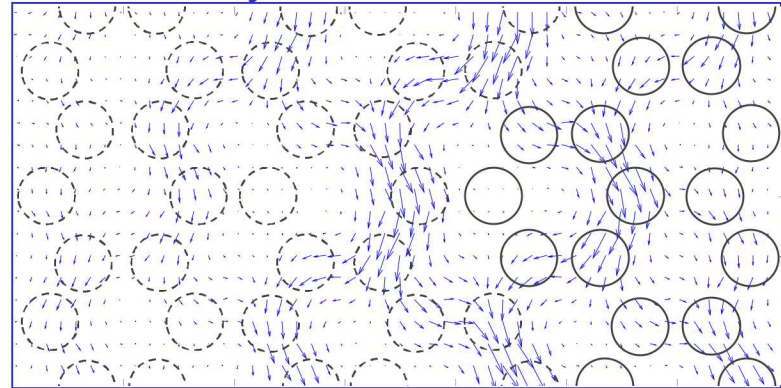
Zig-zag interface



$k_y = -0.05(2\pi/a)$



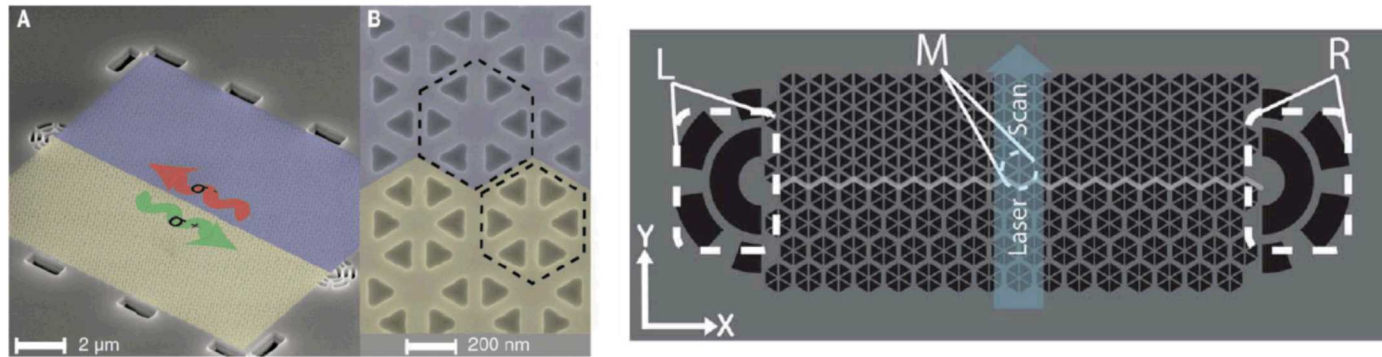
$k_y = 0.05(2\pi/a)$



How to launch a helical source?

Quantum Dot based Helical Sources

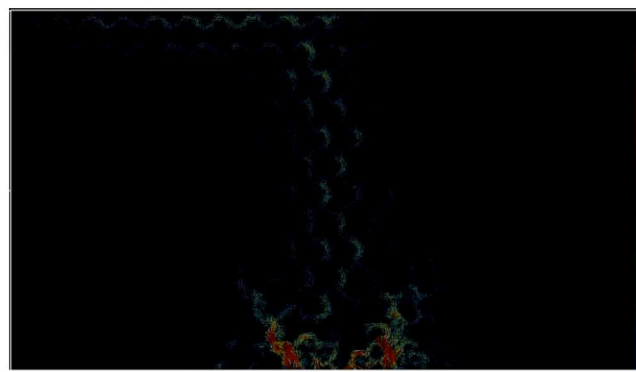
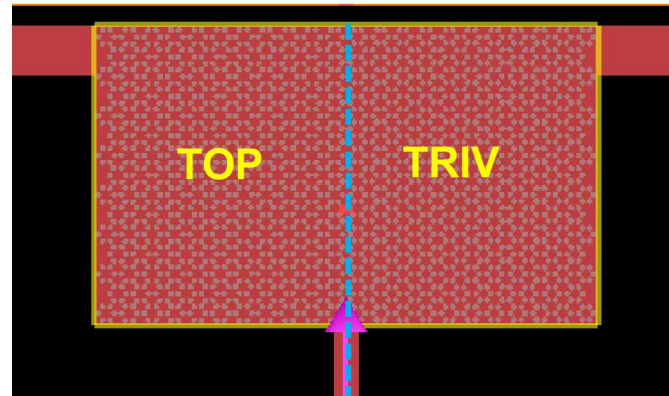
Barik, S., et al. (2018). "A topological quantum optics interface." Science **359**(6376): 666.



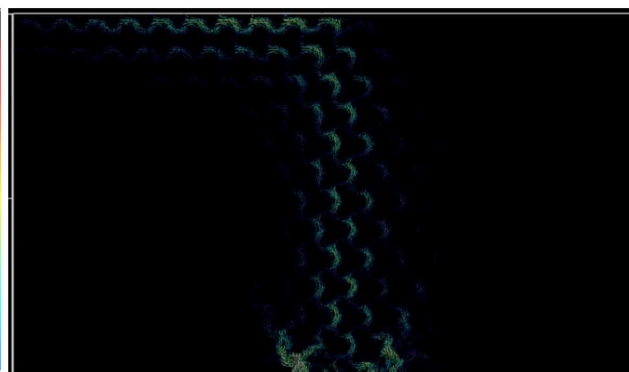
- Create a quantum dot inside the structure
- Apply high B field to split energy level as well as helicity
- Unidirectional propagation of single photon source
- Bandwidth difficult to demonstrate

What about a passive structure to manipulate light incident from elsewhere?

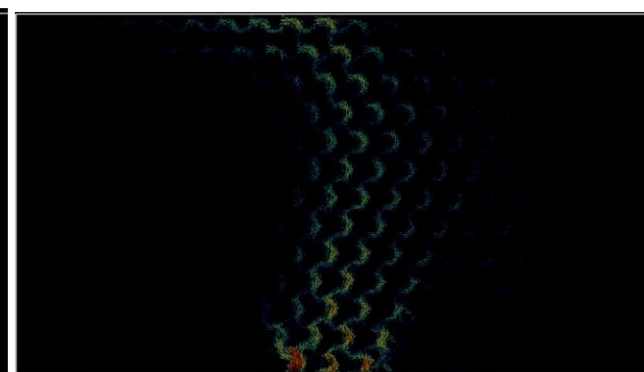
Demonstrating Topological Behavior in a Waveguide System



$a/\lambda \sim 0.557$



$a/\lambda \sim 0.552$

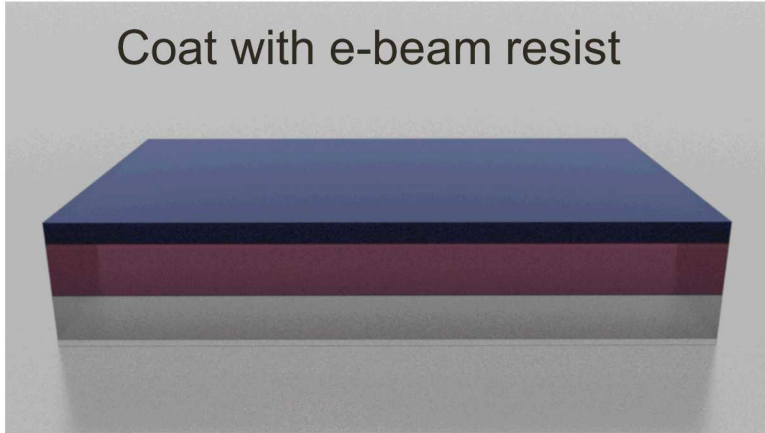


$a/\lambda \sim 0.543$

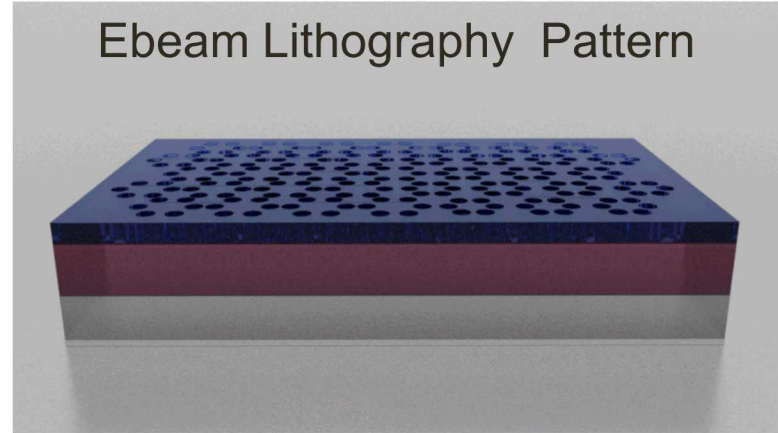
- This can be implemented experimentally
- Can observe the bandwidth of top. behavior

Fabrication on Silicon on Insulator (SOI) - Membrane

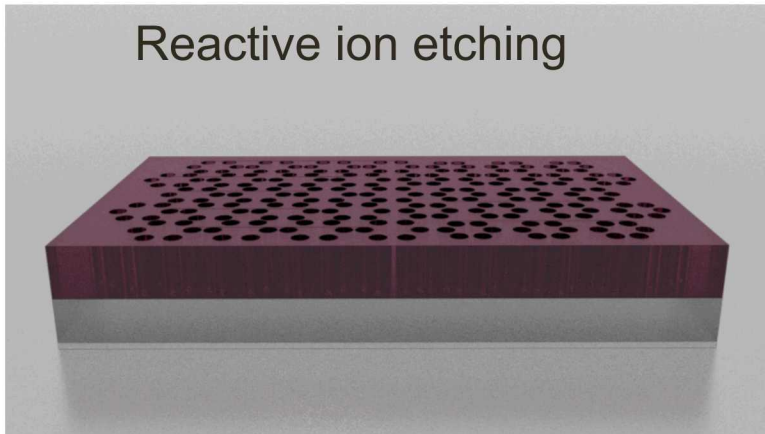
Coat with e-beam resist



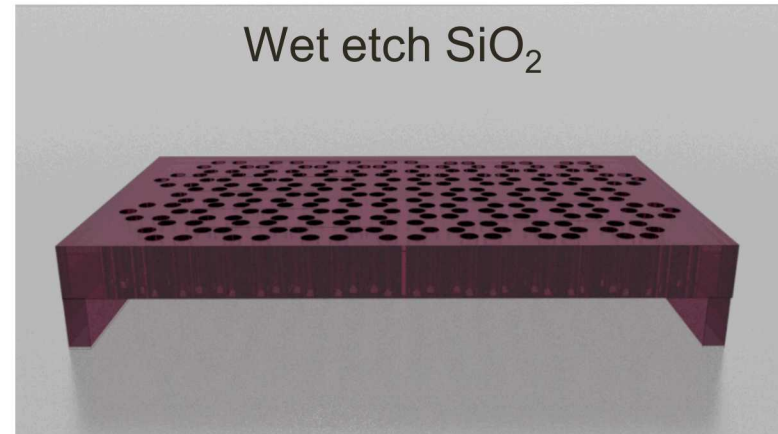
Ebeam Lithography Pattern



Reactive ion etching



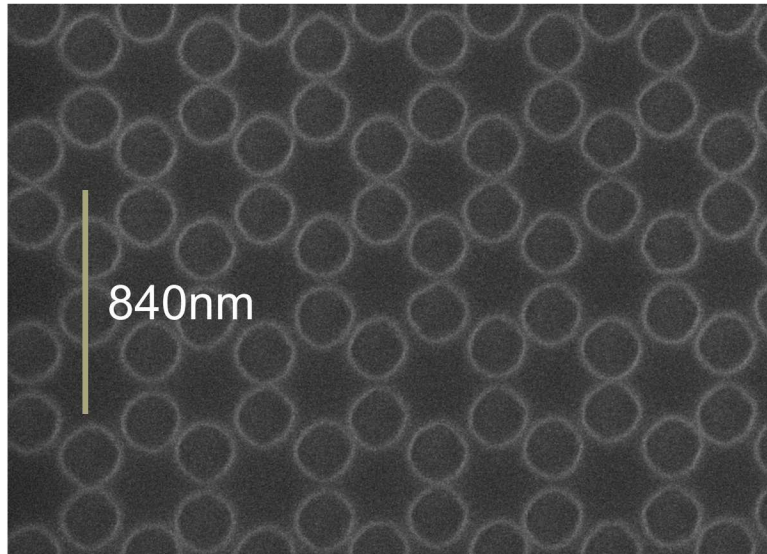
Wet etch SiO_2



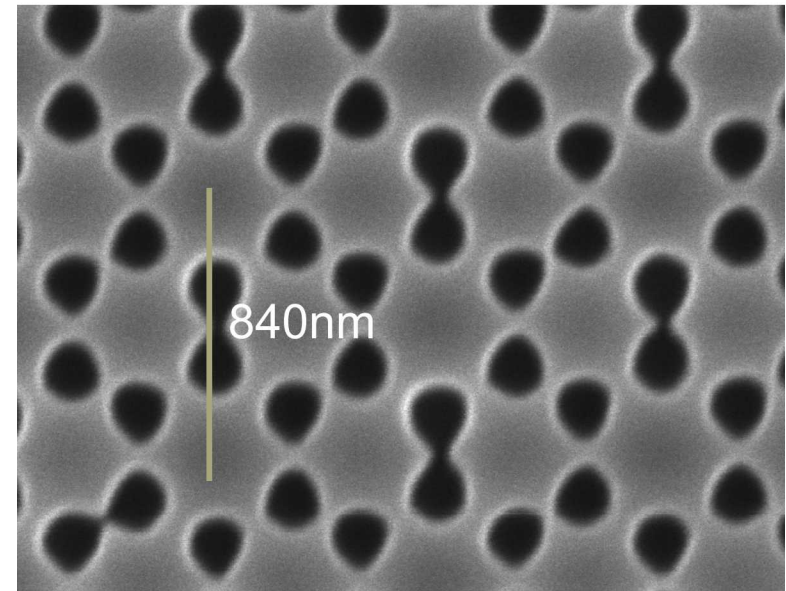
Fabrication on Silicon on Insulator (SOI) - Membrane

- For $\lambda \sim 1500$ operation $a \sim 840\text{nm}$
- Hole radius 'r' = $0.13 \cdot 840 = 110\text{nm}$ or 'd' $\sim 220\text{nm}$
 - Typical feature sizes at the necks $\sim 30\text{-}50\text{nm}$

After pattern write in resist



After pattern transfer

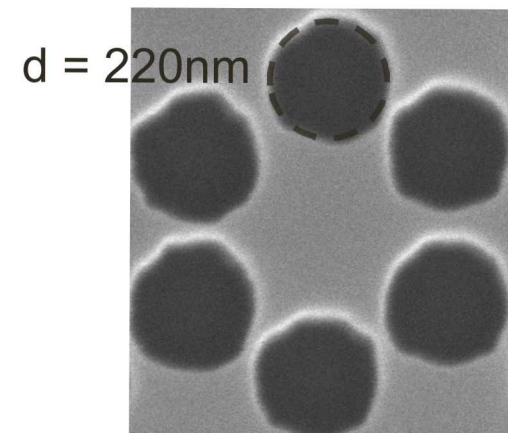
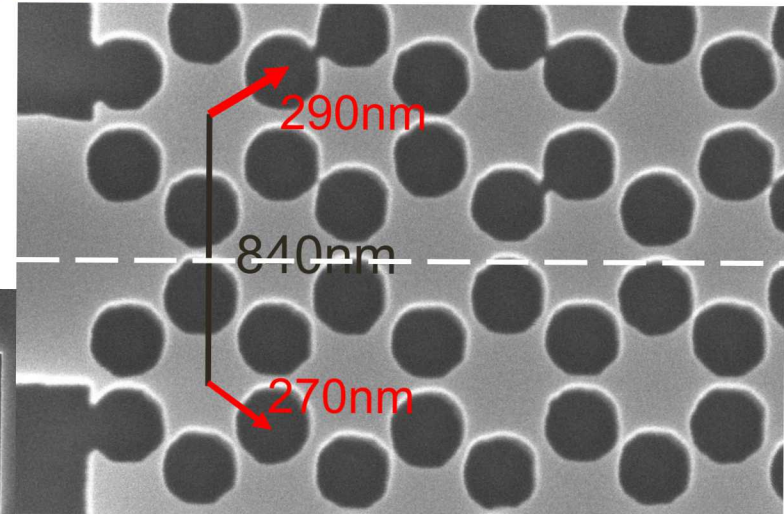
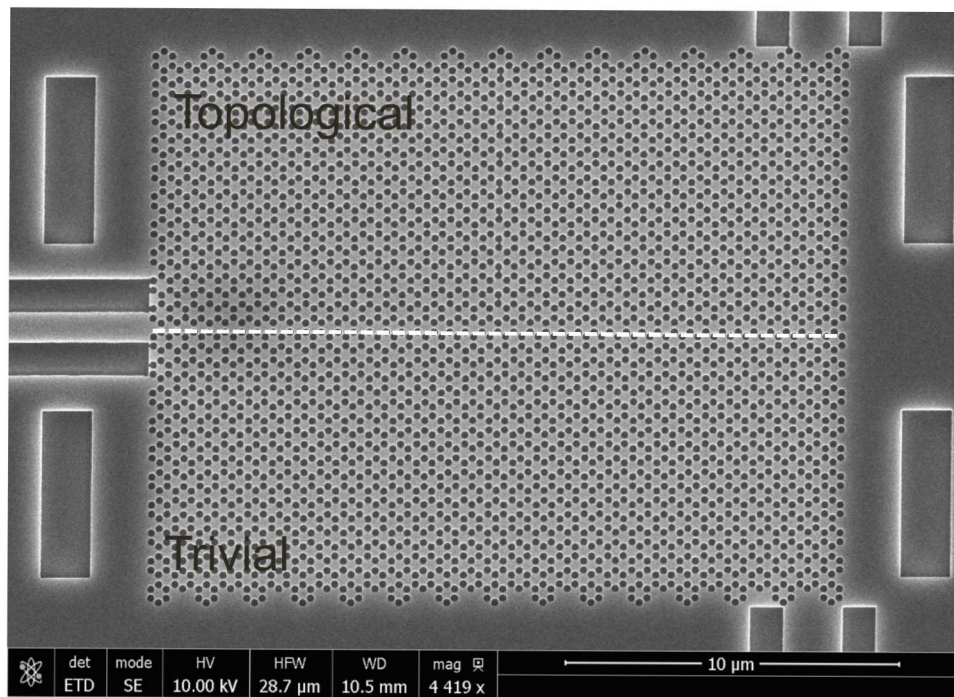


Issues with 'necking' of adjacent holes - addressed with SiO₂ hard mask

Fabrication on Silicon on Insulator (SOI) - Membrane

Pattern transfer to Si

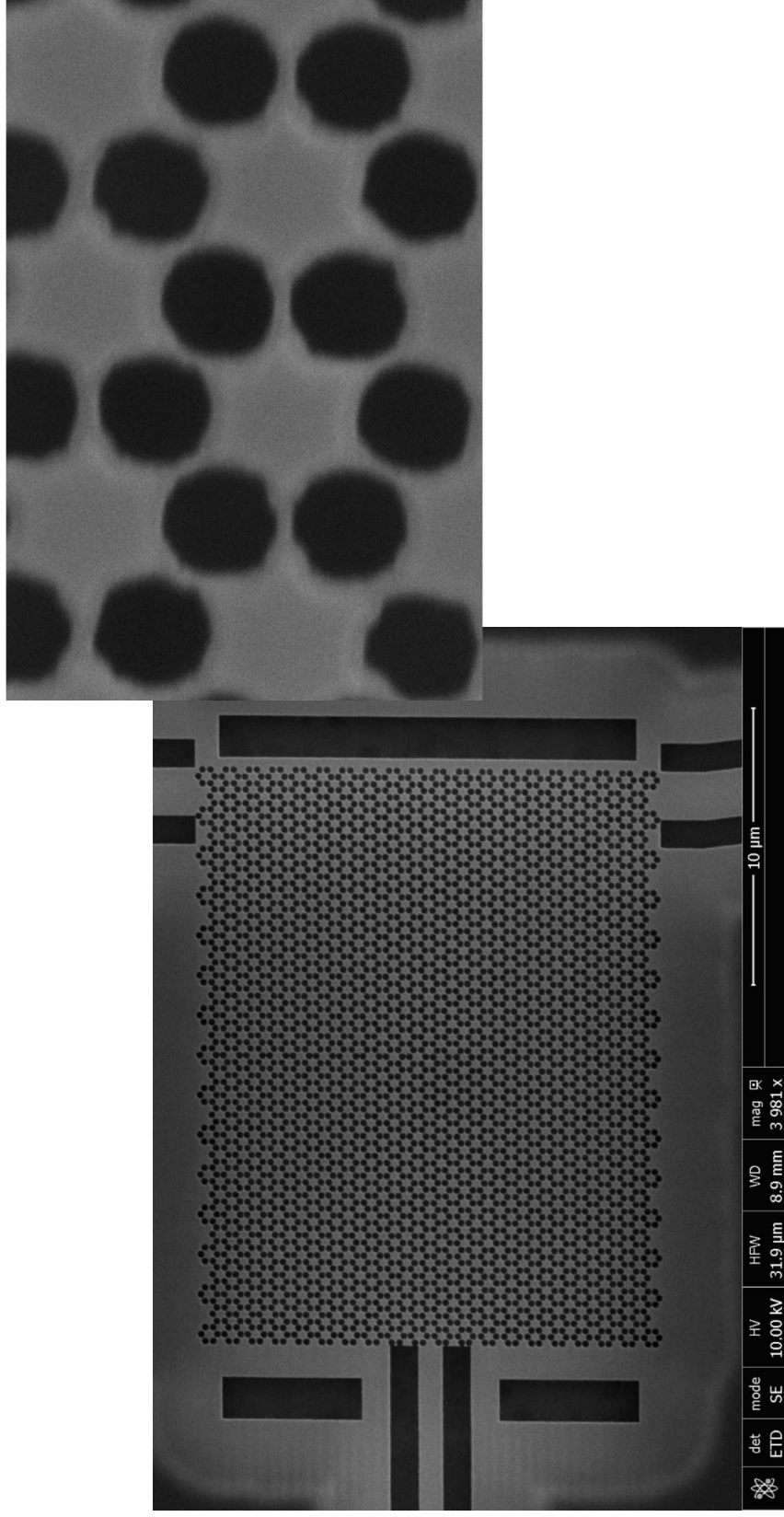
- ~ 50 nm SiO₂ is used as hardmask for pattern transfer
- Highly selective HBr based RIE for Si etch



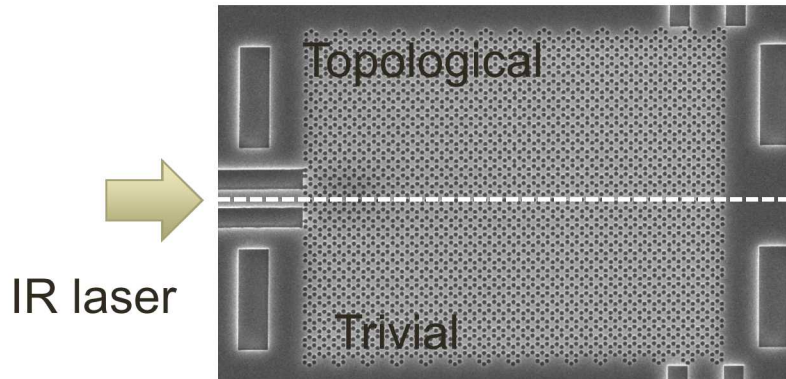
Fabrication on Silicon on Insulator (SOI) - Membrane

Release etch for membrane

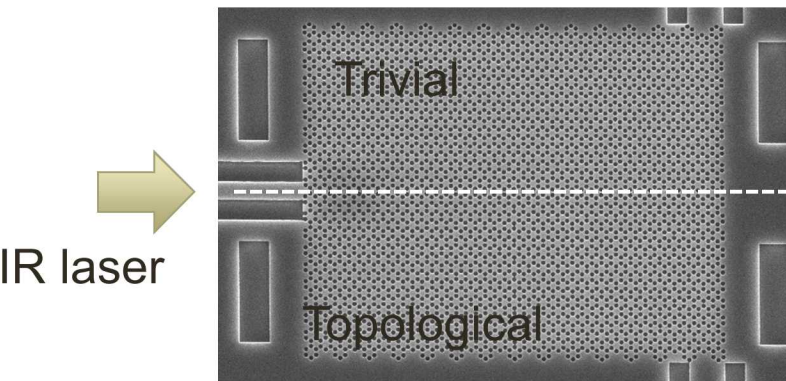
- Reduced etch depth to $\sim 1.0 \mu\text{m}$ shows improvements



Optical Spectroscopy



$\lambda \sim 1536\text{nm}$



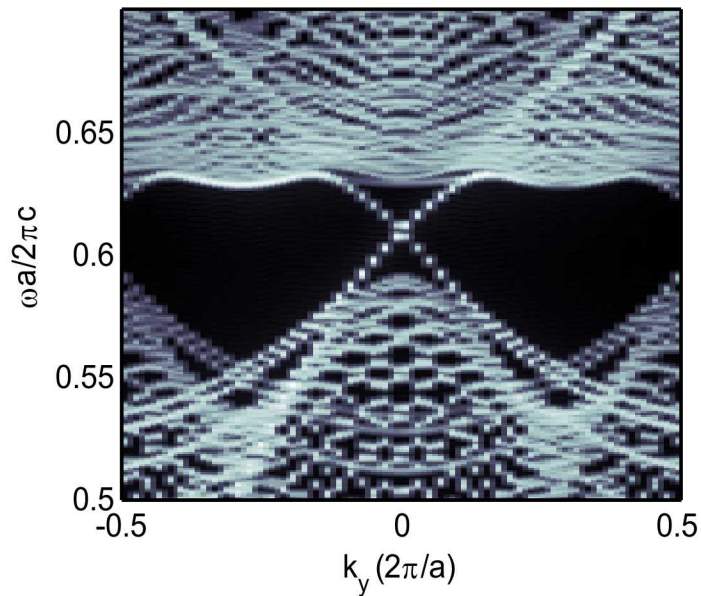
Light propagation shows clear distinction based on orientation of the Topological PhC relative to the Trivial PhC

III –nitride based structures for Active Topological PhCs

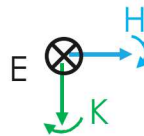
Topological edge state in honeycomb lattice structure in III-Nitride

Modeling

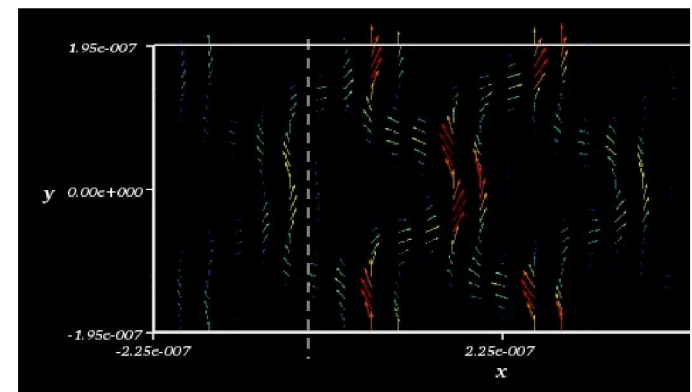
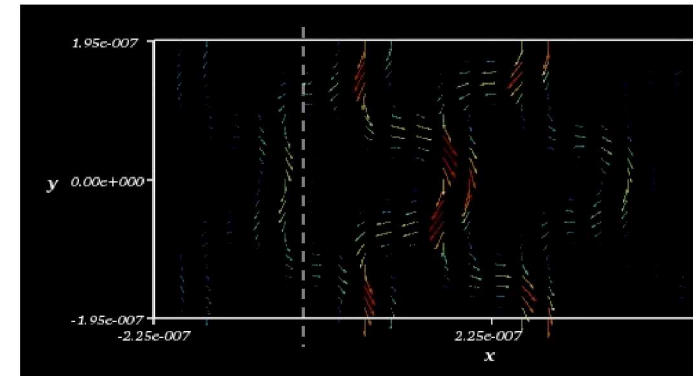
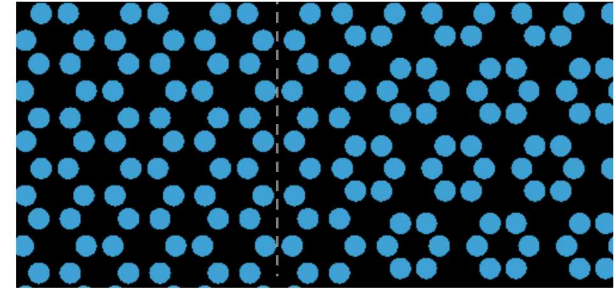
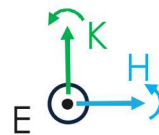
Band Structure



Spin-down state
 $a/\lambda = 0.618$

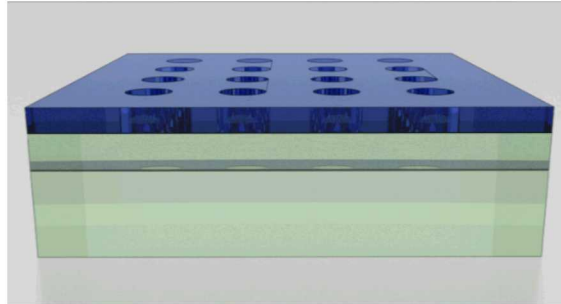


Spin-up state
 $a/\lambda = 0.60$

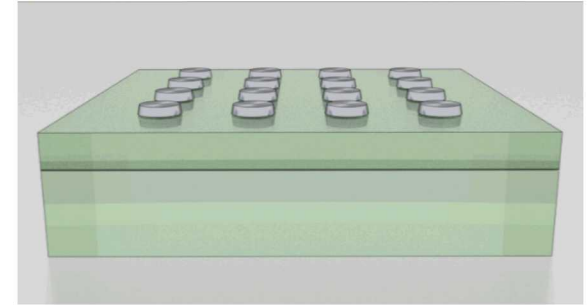


Fabrication procedure in GaN

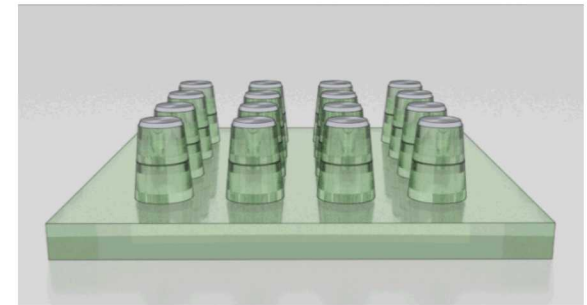
EBL pattern in
PMMA



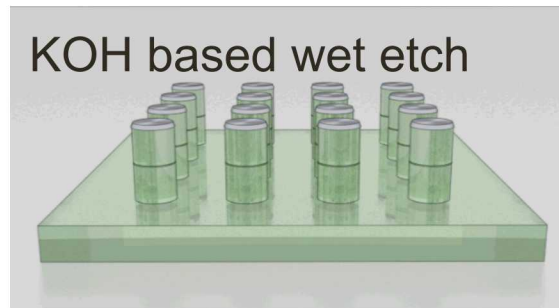
Ni evaporation and lift-off



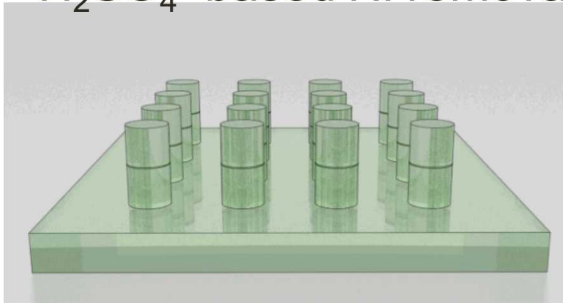
Cl₂ based dry etch



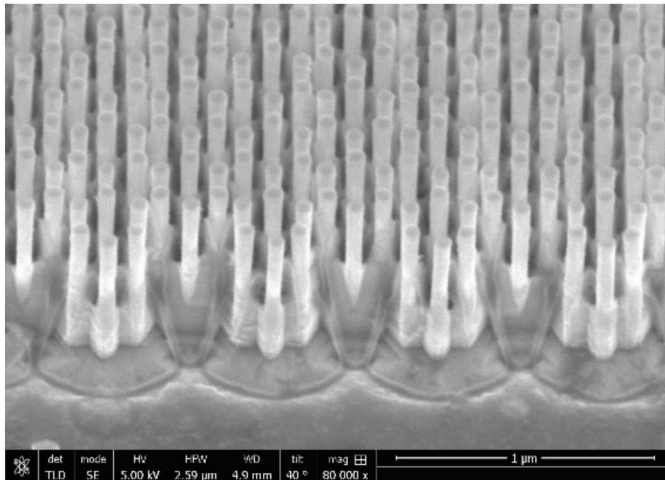
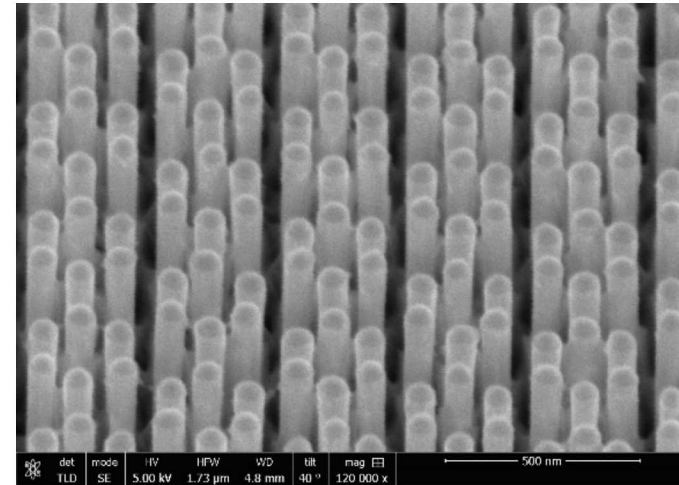
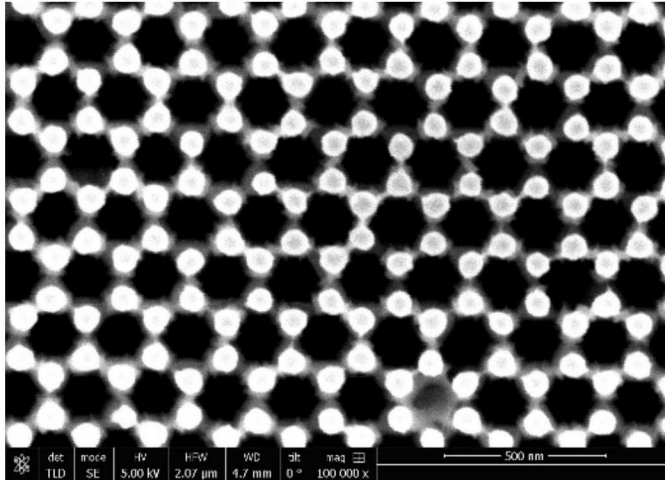
KOH based wet etch



H₂SO₄-based Ni removal



Topological/Trivial lattice interface structure in III-Nitride



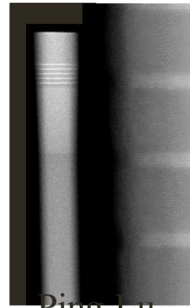
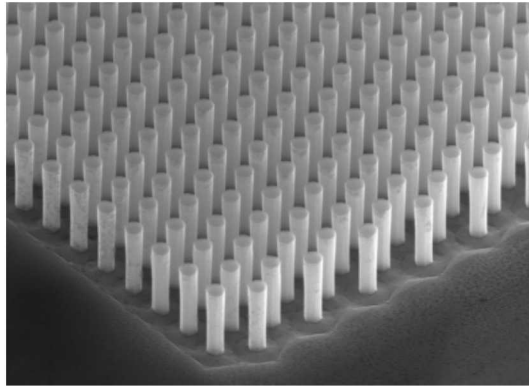
Ongoing ...

- ❑ Main challenges
- ❑ Deeper etching

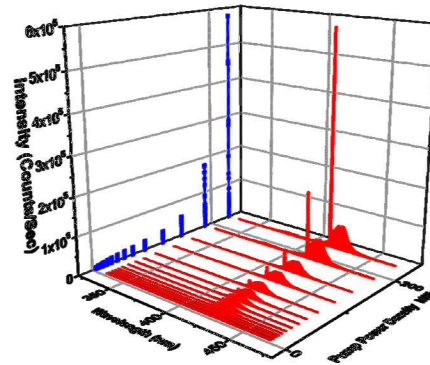
Topological structure in active material systems

PhC nanrod array have shown excellent light emission behavior

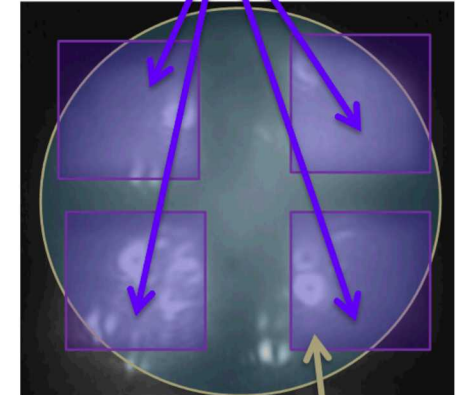
Demonstration of Lasing from PhC Array



Ping Lu,
Sandia



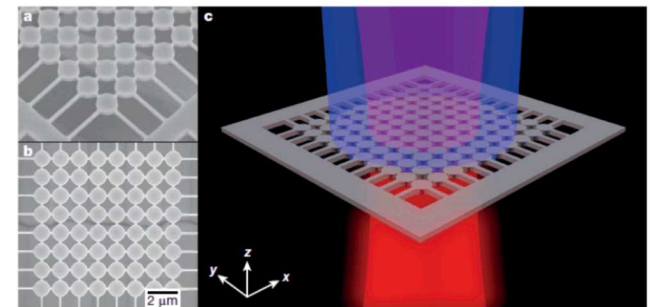
Photonic Crystal Laser Pixels



Pump Spot

J. B. Wright et.al., Sci. Rep. **3**, 2982 (2013).

Fabricated by using a top down approach from a planar GaN with InGaN Multiple quantum wells

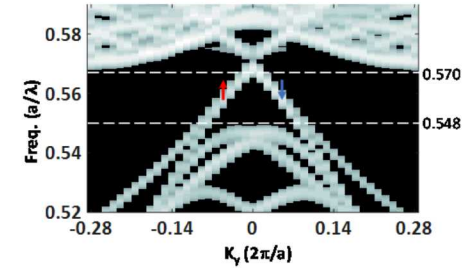
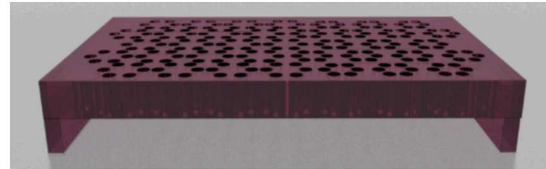


Light sources with topological charges?

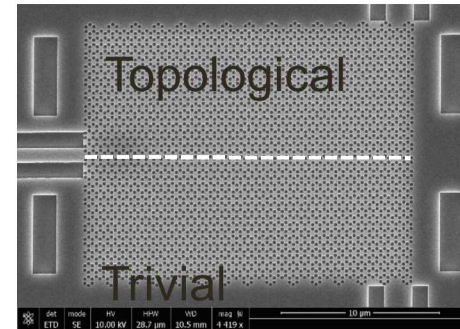
A. Kodigala, et.al," Nature **541**, 196-199 (2017).

Summary

- Hole array honey comb lattice structure for photonic pseudo spin



- Fabrication in Silicon/SOI



- Fabrication in III-N

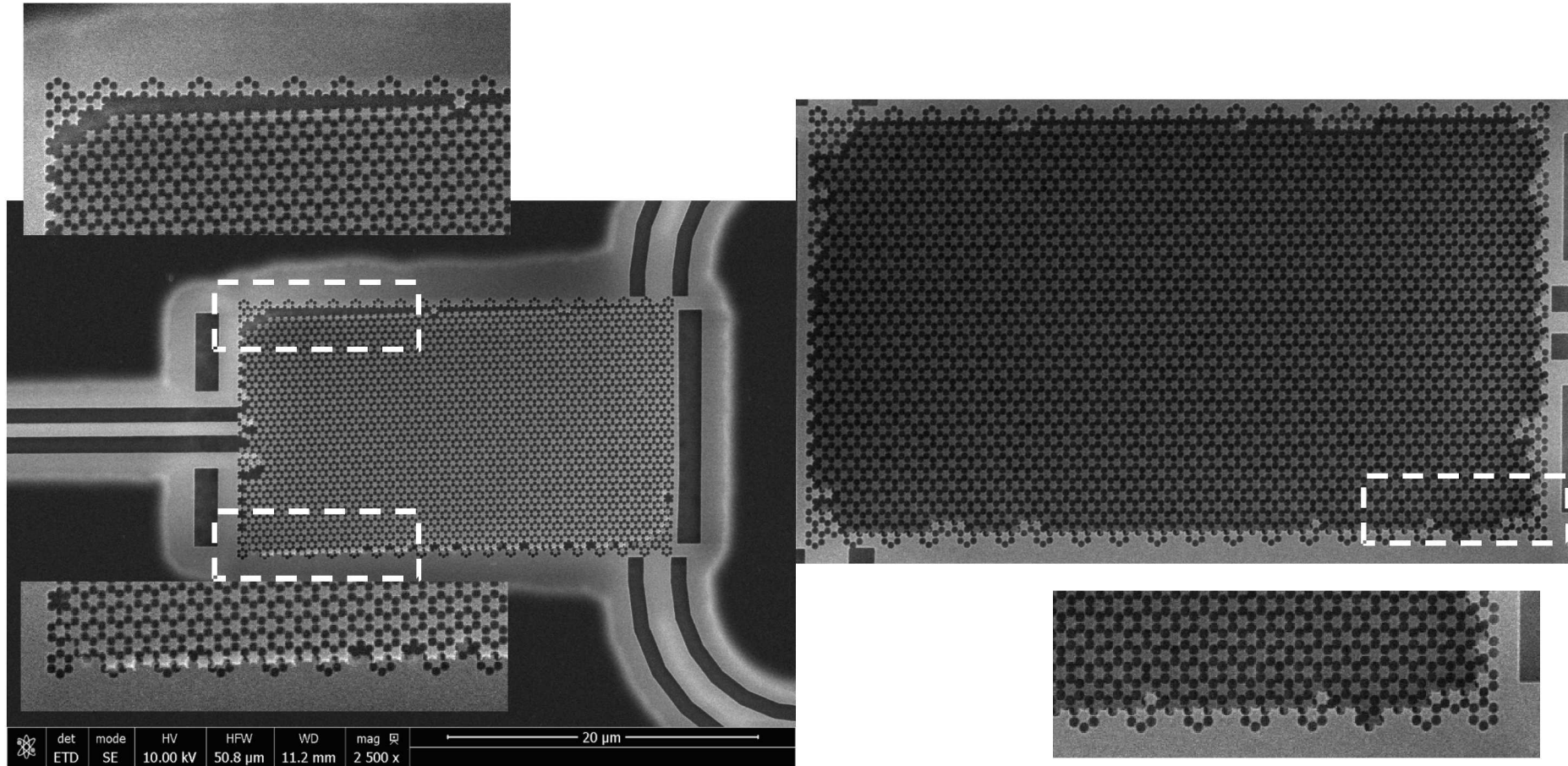
Thank you for your attention!

Extras ...

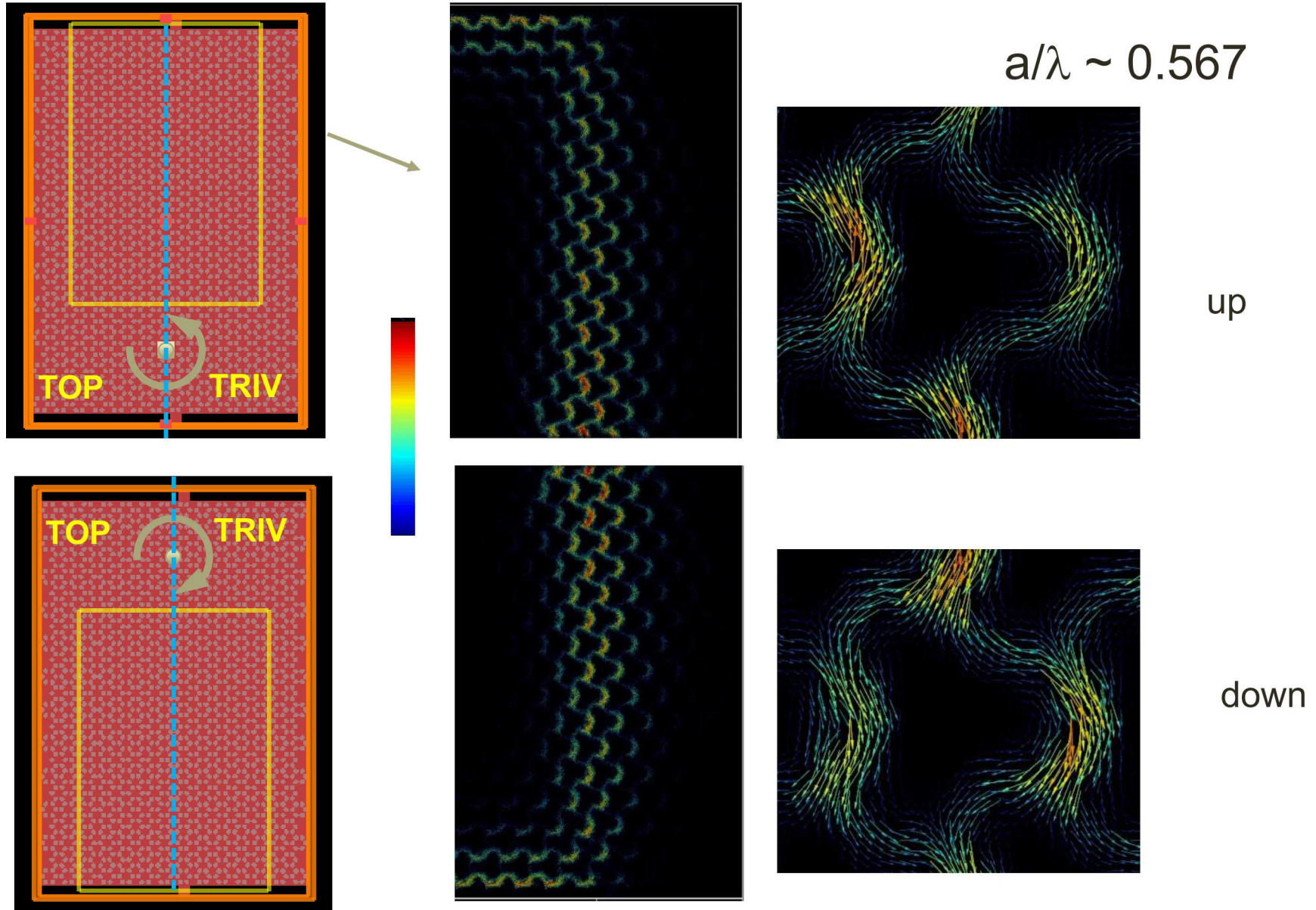
Fabrication on Silicon on Insulator (SOI) - Membrane

Release etch for membrane

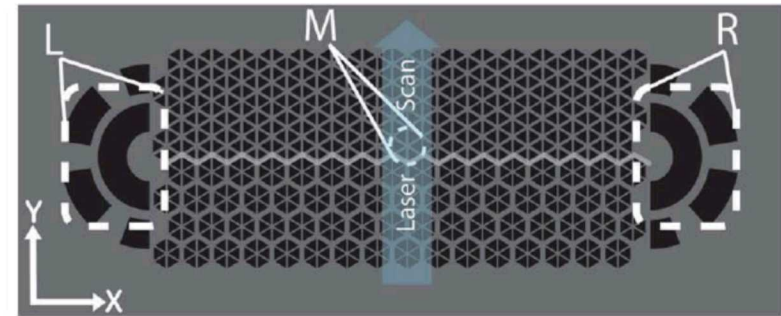
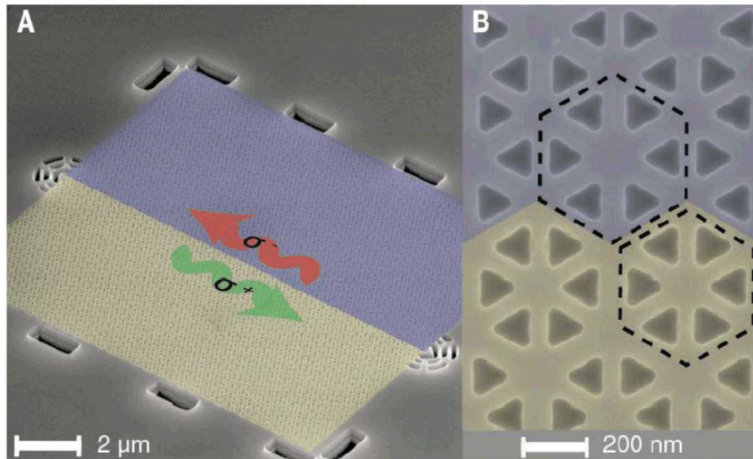
- Wet etch in buffered oxide etchant for 15-20min : 1.6 to 1.8 μm deep
- Narrow bridge necks + Si epi stress causes some challenges



Unidirectional Propagation with Helical Sources



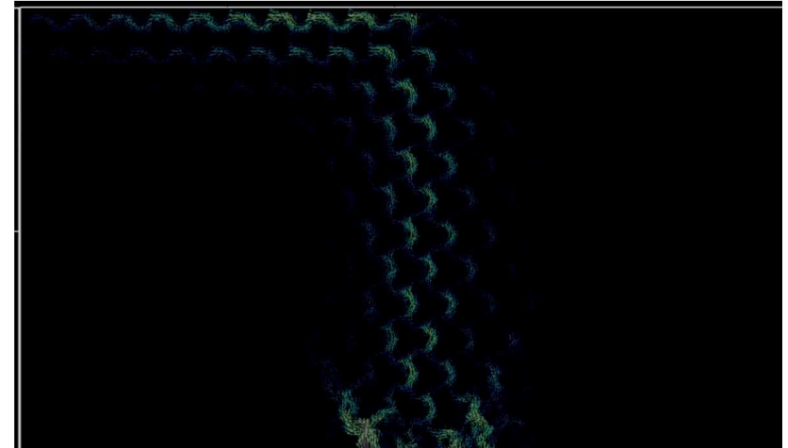
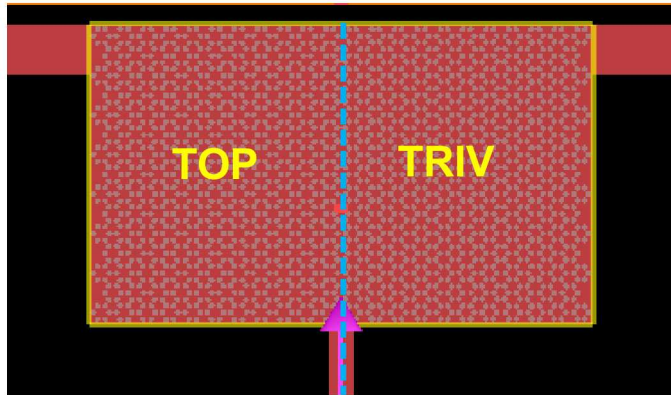
Quantum Dot based Helical Sources



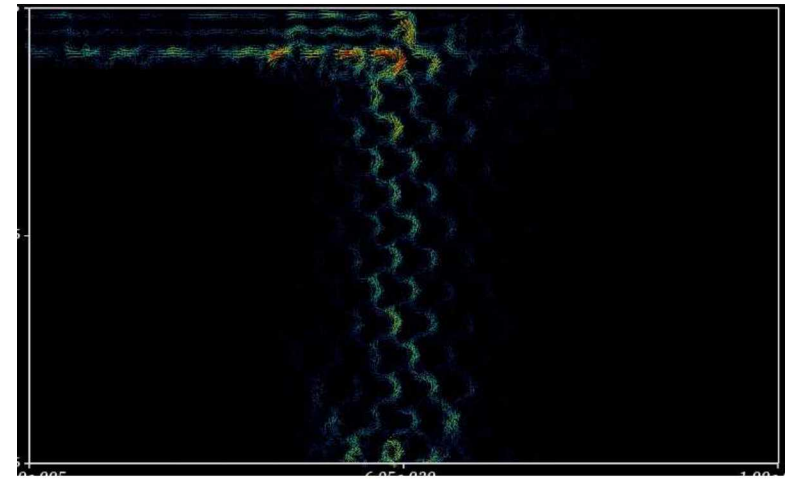
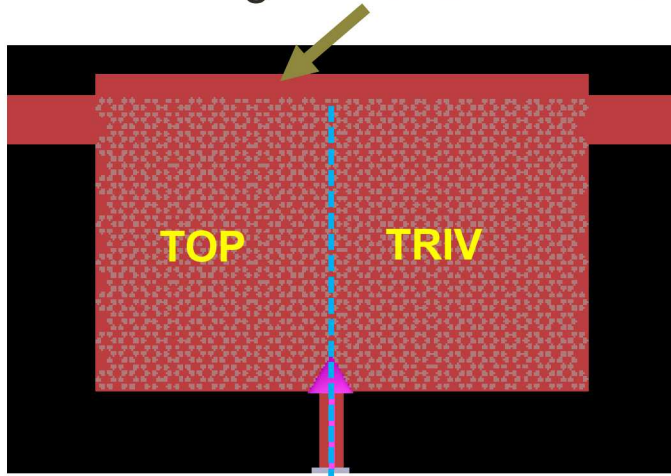
Barik, S., et al. (2018). "A topological quantum optics interface." *Science* **359**(6376): 666.

- Create a quantum dot inside the structure
- Apply high B field to split energy level as well as helicity
- Unidirectional propagation of single photon source
- Bandwidth difficult to demonstrate

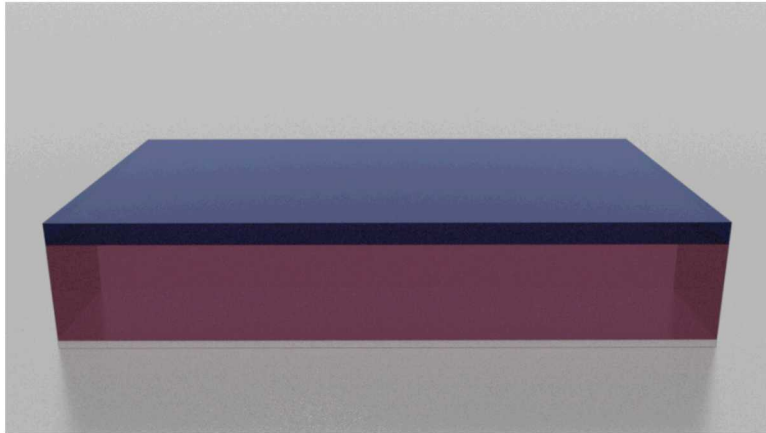
What about a passive structure to manipulate light incident from elsewhere?



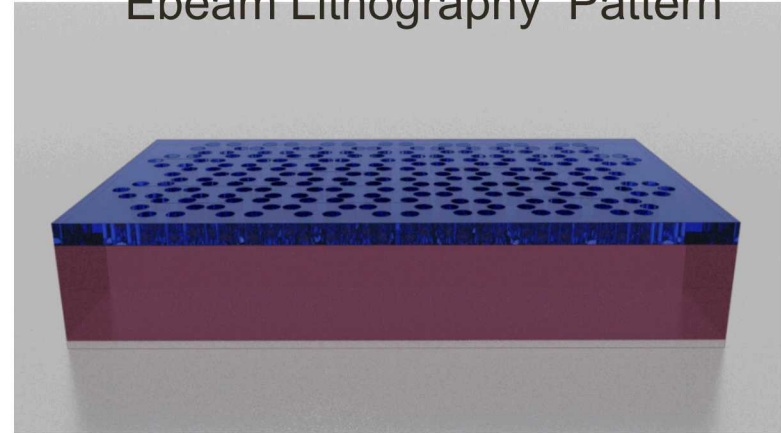
High index trivial medium



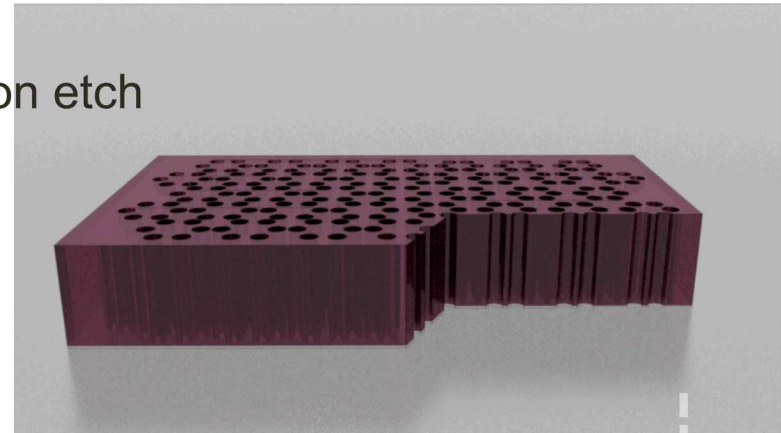
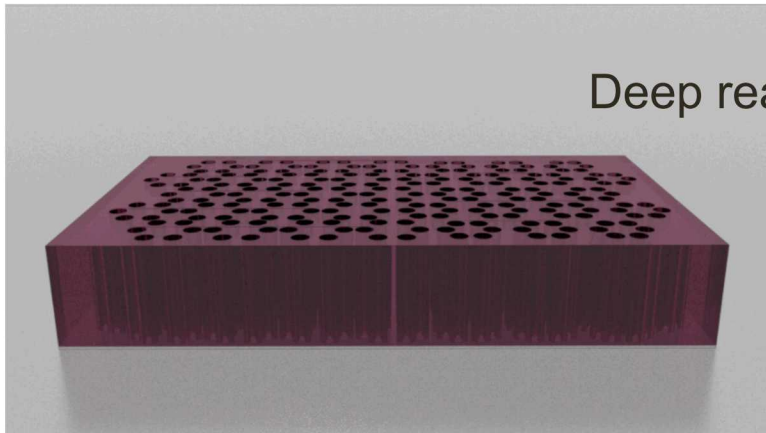
Fabrication on Thick Si using deep etch



Ebeam Lithography Pattern



Deep reactive Ion etch



This can be challenging fabricate and may not always be compatible with typical Si photonics designs.